

Materials List for:

Dry Oxidation and Vacuum Annealing Treatments for Tuning the Wetting Properties of Carbon Nanotube Arrays

Adrianus Indrat Aria¹, Morteza Gharib¹

¹Graduate Aeronautical Laboratories, California Institute of Technology

Correspondence to: Adrianus Indrat Aria at indrat@caltech.edu

URL: <https://www.jove.com/video/50378>

DOI: [doi:10.3791/50378](https://doi.org/10.3791/50378)

Materials

Name	Company	Catalog Number	Comments
Lindberg Blue M Mini-Mite tube furnace	Thermo Scientific	TF55030A	1" tube furnace for CNT array growth
Electronic mass flow controllers	MKS	PFC-50 πMFC	Max flow rate of 1000 sccm
Electronic pressure controller	MKS	PC-90 πPC	Max pressure of 1000 Torr
1" quartz tube	MTI Corp.	>EQ-QZTube-25GE-610	1" D x 24" L
Hydrogen gas	Airgas	HY UHP200	CNT array growth precursor gas, 99.999% purity
Ethylene gas	Matheson	G2250101	CNT array growth precursor gas, 99.999% purity
Argon gas	Airgas	AR UHP200	CNT array growth precursor gas, 99.999% purity
Silicon wafer	EI-Cat	2449	With 300 nm polished thermal oxide layer
Iron pellets	Kurt J Lesker	EVMFE35EXEA	99.95% purity
Aluminum oxide pellets	Kurt J Lesker	EVMALO-1220B	99.99% purity
E-beam evaporator	CHA Industries	CHA Mark 40	For buffer and catalyst layer deposition
UV/ozone cleaner	BioForce Nanosciences	ProCleaner Plus	For oxidizing CNT array
Oxygen plasma cleaner	PVA TePla	M4L	For oxidizing CNT array
Vacuum oven	VWR	97027-664	For deoxidizing CNT array
SEM	Zeiss	1550 VP	For CNT array growth characterization
XPS	Surface Science	M-Probe	For surface chemistry characterization
Contact angle goniometer	ramé-hart	Model 190	For wetting properties characterization